

Free-Charge Carrier Profiles of Iso- and Anisotype Si Homojunctions

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P2-10

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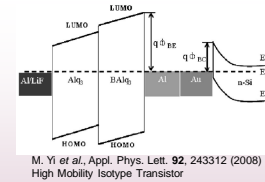
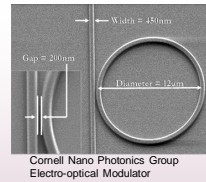
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Our Message

- We demonstrate the first desktop THz ellipsometer in the frequency range from 0.1 to 1.5 THz (3 to 50 cm⁻¹) using a rotating analyzer configuration and a tunable backward wave oscillator source.
- THz ellipsometry enables optical determination of low (!) (~10¹⁵ cm⁻³) free charge carrier concentrations in silicon bulk and layered structures.
- THz ellipsometry can be used to accurately find the location of an abrupt isotype (p+/p or n+/n) homojunction as well as the diffused carrier concentration profile.
- Simultaneous analysis of THz and FIR data allows contact-free, non-destructive measurement of complex semiconductor structures.

Motivation

- Optical sensitivity to low carrier concentration levels via THz resonance polaritons provides a new technique to study complex semiconductor structures
- Non-destructive, contact-free determination of semiconductor structure is key to developing future technologies

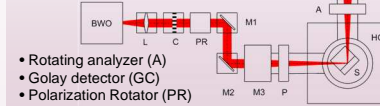


- Integrated Circuit waveguides for photonic computation and integration with optical fiber communications
- High mobility transistors
- Silicon homojunction interfacial workfunction internal photoemission (HIWIP) far-infrared detectors

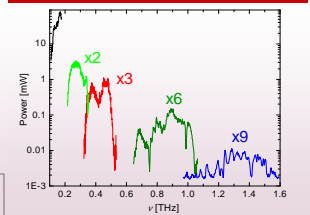
THz Ellipsometry Setup



Patent application filed with UNL, Sept. 2008



Backwards Wave Oscillator (BWO) Source



Output power of the BWO augmented with different Schottky diode multipliers

Model System

Spectral Features

- The low THz region is dominated by surface guided waves, present here at ~290 GHz and ~900 GHz.
- The FIR region is dominated by Fabry - Perot oscillations, which damp at high frequency.

Analytical Model

Analytical solution to Poisson equation of an isotype homojunction [1]:

$$E^2(\phi) = -2/(\epsilon_0 \epsilon) \int \rho(\phi) d\phi$$

Assuming semi infinite boundary conditions and substituting the non-degenerate semiconductor expressions:

$$N(x) = N_D e^{(q\phi(x)/kT)} \quad P(x) = N_A e^{(q\phi(x)/kT)}$$

Results in a simplified equation if $N_+ \gg N_-$, where $N(x)$ may be determined entirely in terms of N_+ and N_- and a characteristic length L :

$$N_H(x) = N_+ e^{-\left[\frac{LN(N_+/N_-)}{1 + \sqrt{N_+/N_-}} \right] x/L}$$

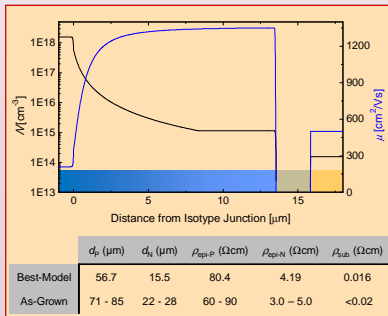
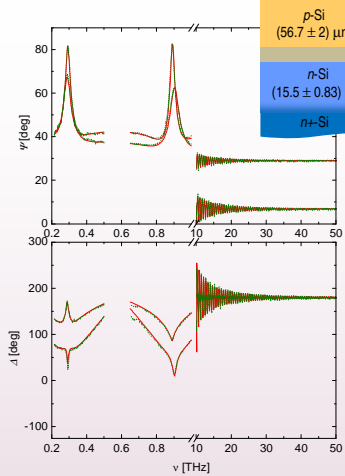
$$N_L(x) = N_- e^{-\left[LN\left(\frac{N_-}{N_+}\right) - 2LN(e^{0.5} \left(1 - \frac{N_- LN(N_+/N_-)}{N_+ - N_-}\right) + x/L) \right]}$$

Separate solutions for each side of the abrupt dopant junction lead to an asymmetric carrier profile. Mobility is also given as a function of concentration [2].

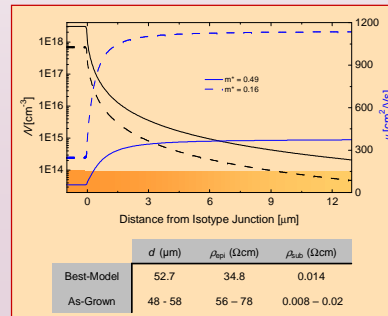
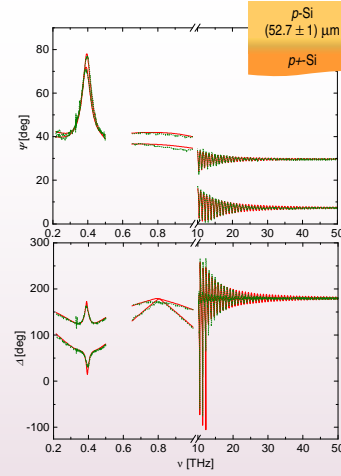
$$\mu = \mu_{min} + \frac{\mu_{max} - \mu_{min}}{1 + \left(\frac{N}{N_{ref}}\right)^m}$$

[1] Z.T. Kuznicki, J. Appl. Phys. **69**, 6526 (1991)
 [2] C. Jacoboni et al., Solid-State Electron. **20**, 77 (1976)

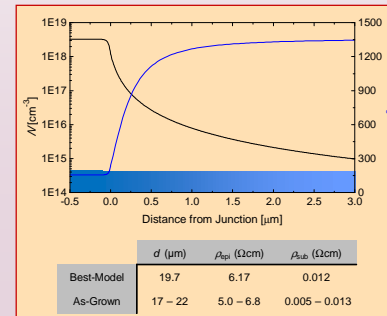
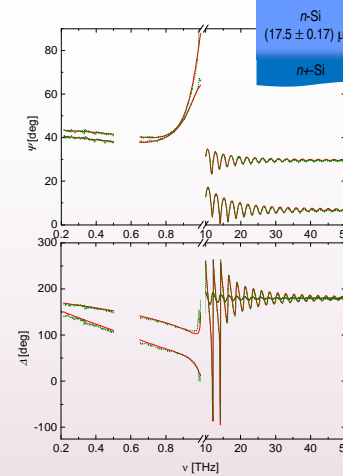
P/N/N+ Sample



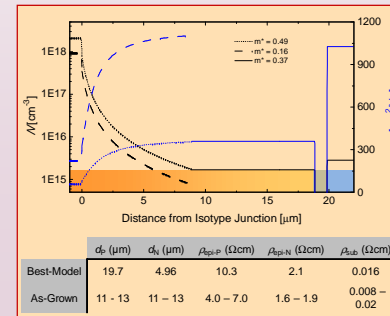
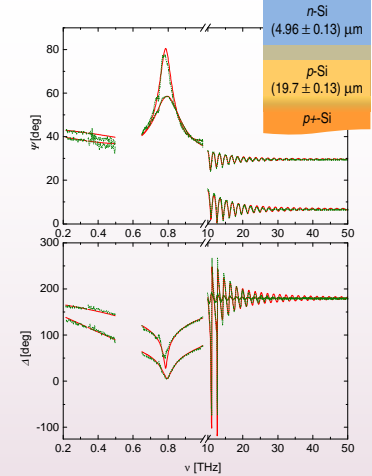
P/P+ Sample



N/N+ Sample



N/P/P+ Sample



Silicon Iso- and Anisotype Example Systems